

DOCKET NO. 108430.030B . Sheet 1 of 1 Serial No. 10/091,011 CLEANING AND DRYING METHOD AND APPARATUS Applicant: Ismail Kashkoush Replacement for FIG. 1

Process: SC1/R/HF/R/LuCID
(2 bare Si wafers per test sandwiched with 23 TOX wafers)

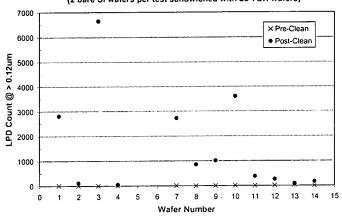


Fig. 1 (Prior Art)